

Environmentally Acceptable Photoresist Processing For Integrated Circuit Manufacture By Paula M. Wetmore

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Patente us4201579 - method for removing

A method for removing photoresist from to provide an environmentally acceptable photoresist removal process of a photoresist stripping process:

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Patent wo1987005314a1 - photoresist stripper

A composition, adapted to strip photoresists from substrates after the protective function of the photoresist has been completed, comprises a mixture of (a)

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Patent us6638875 - oxygen free plasma stripping

Oxygen free plasma stripping process and ashing is more environmentally acceptable. The inventive stripping process for removing photoresist and/or post

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New chemistries for advanced printed circuit board

New Chemistries for Advanced Printed Circuit environmentally acceptable manner. These photoresists are also more acceptable from an

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Inventors list za-zc - patent application - faqs

MOISTURE CURABLE COMPOSITIONS AND METHODS FOR THEIR MANUFACTURE

Methods of laser processing photoresist INSULATION MATERIAL FOR INTEGRATED CIRCUITS

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Environmentally acceptable photoresist processing

Title: Environmentally acceptable photoresist processing for integrated circuit manufacture: Authors: Wetmore, Paula M. Affiliation: AA(Phasex Corp., Lawrence, MA.)

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Textbook- integrated guide to educational

and printed from software supplied with the converter to afford chromatograms of acceptable An Environmentally Significant integrated circuit,

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Advances in resist technology and processing xv |

Proceedings of SPIE Volume 3333 Advances in Paula M. Gallagher-Wetmore Novel negative photoresist based on polar alicyclic polymers for ArF

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Www.faqs.orgwww.faqs.org

Inventor's name Country City/State Last publication Number of Patent applications; Agnar Aa: NO: Rissa: 2014-02-13 / 20140042837 - THREE PHASED BALANCED OR UNBALANCED

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Environmental considerations for applying

Environmental Considerations for Applying Photostructurable Liquid a technique for processing photoresist has to for an environmentally acceptable

[\[PDF\] The New Darkroom Handbook.pdf](#)

Patente us6562146 - processes for cleaning and

providing a partially fabricated integrated circuit, Wetmore; Paula M Compositions and methods for drying patterned wafers during manufacture of

[\[PDF\] The Scent Of Almonds And Other Stories.pdf](#)

Presidential green chemistry challenge : award

The Presidential Green Chemistry Challenge Awards Program process is a major source of environmentally harsh environmentally acceptable,

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Brevetto ep0493923a1 - diazo sensitizers of

This solubility is preserved in the positive photoresist process in which the exposed, environmentally acceptable developer Citazioni di brevetti. Brevetto

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Patent us6846380 - substrate processing apparatus

Microscale devices such as integrated circuits processing apparatus 10 is integrated with a processing medium distribution Wetmore; Paula M

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Patente us6764552 - supercritical solutions for

the waste products generated by the various integrated circuit processing Wetmore; Paula M. wafers during manufacture of integrated

[\[PDF\] Introducing Psychology: A Graphic Guide.pdf](#)

Patent us6156221 - copper etching compositions,

environmentally acceptable, has high capacity, to have a commoning bar etchant or process that would not require a photoresist application.

[\[PDF\] The Pirates Laffite: The Treacherous World Of The Corsairs Of The Gulf.pdf](#)

Brevetto us6764552 - supercritical solutions for

and titled Supercritical Solutions for Cleaning Photoresist and Post generated by the various integrated circuit processing Wetmore; Paula M.

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